Exhibitor Technology Spotlight
Room: Hall 1 - Session EW-WeM

Exhibitor Technology Spotlight Session
Moderator: Dennis Sollon, Kurt J. Lesker

10:20am **EW-WeM8 New and Ongoing Developments in Thin Film Deposition from the Kurt J. Lesker Company®**, *S. Armstrong*, ***Duane Bingaman***, *B. Zinn*, Kurt J. Lesker Company

This presentation will cover the latest developments in deposition sources and PVD and ALD thin film deposition systems. New advances in the field of vacuum deposition science will be outlined with a Q&A session to follow.

10:40am **EW-WeM9 H2O2 Gas: Revolutionary new molecule for ALD**, ***Jeffrey Spiegelman***, *D. Alvarez*, RASIRC

H2O2 is well known for its superior oxidizing capabilities. Now H2O2 is available in high concentration, with or without water and even without carrier gas. H2O2 gas is ideal for next generation materials and 3D architectures that are temperature and water sensitive. Learn about two innovative products that overcome Raoult's Law and deliver stable, repeatable, high concentration H2O2 gas. The Peroxidizer delivers up to 5% H2O2 gas by volume from 30% H2O2 liquid solution. BRUTE Peroxide delivers anhydrous H2O2 gas for water sensitive processes such as ALD involving new materials and 3d architectures.

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